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PROGRAMMER'S MANUAL FOR THE BANNING ARTWORK PROGRAM

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Prepared for

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16. ABSTRACT This document is intended to serve as the programmer's Manual for the Banning Artwork Program. A detailed description of the internal logic and flow of the Artwork Program has been included in this report. It is recommended that every user review this manual in order to receive an appreciation of the functions performed by the Artwork Program; however, the User's Manual for the Artwork Program contains sufficient information to allow the designer/engineer to efficiently use the Artwork Program. Before beginning a detailed study of this Programmer's Manual, the reader should have a complete understanding of the contents of the User's Manual for the Banning Artwork Program. It is assumed that the programmer using this manual has a working knowledge of FORTRAN IV.					
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REFERENCE

This document is primarily a rewrite of information contained in the original documentation for the Artwork Program produced by the Radio Corporation of America during the contract for the initial definition and implementation of the Banning System of Programs (Contract Number DA-18-119-AMC-03460(X)).

This "Programmer's Manual" and the "User's Reference Manual" serve as the final documentation of the Banning Artwork Program as implemented by M&S Computing, Inc. under contract number NAS8-25621 for Marshall Space Flight Center's Astrionics Laboratory, Technology Division.

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SECTION I

INTRODUCTION

The Banning Artwork Program generates the Gerber commands that select the appropriate apertures and determine the plotter motions required to completely expose or "fill-in" the specified areas of a circuit mask. The program generates the commands required to produce the artwork of one mask level at a time up to a maximum of nine (9) levels. After each level of artwork has been created, an end-of-file is written on the output magnetic tape and the program recycles to generate the commands needed to create the next level mask.

The structure of the Banning Artwork Program consists of an executive program maintaining control at all times, with subordinate subroutines being called upon to execute the specific requirements for updating the pattern library and creating circuit masks. Figure 1.1 illustrates the functional flow of the Artwork Program through the various subroutines. All program control cards are read and interpreted by the executive routine.

After the title card has been read, the available apertures have been defined to the program, and the fill techniques have been specified, control is passed to the utility subroutine to perform any utility operations required by the current job. The utility subroutine will normally return control immediately to the program executive, but utility requirements may dictate that the pattern library be updated or other utility functions be performed prior to returning control to the main program.

When control is returned to the executive routine, additional control cards are read to determine the number of levels of artwork to draw, and to define any pattern sets that will appear later in the component input data. After the pattern sets have been defined, the component input data is read and formatted into data arrays that can be easily accessed during the mask creation phase of the program.

The remainder of the artwork program consists of the major artwork processing loop that is repeated for each required mask level. The loop performs the following processing for each level:

- Extract the polygons from the pattern library that define the artwork required to construct the masks of each component;

ARTWORK PROGRAM SUBROUTINE FLOW

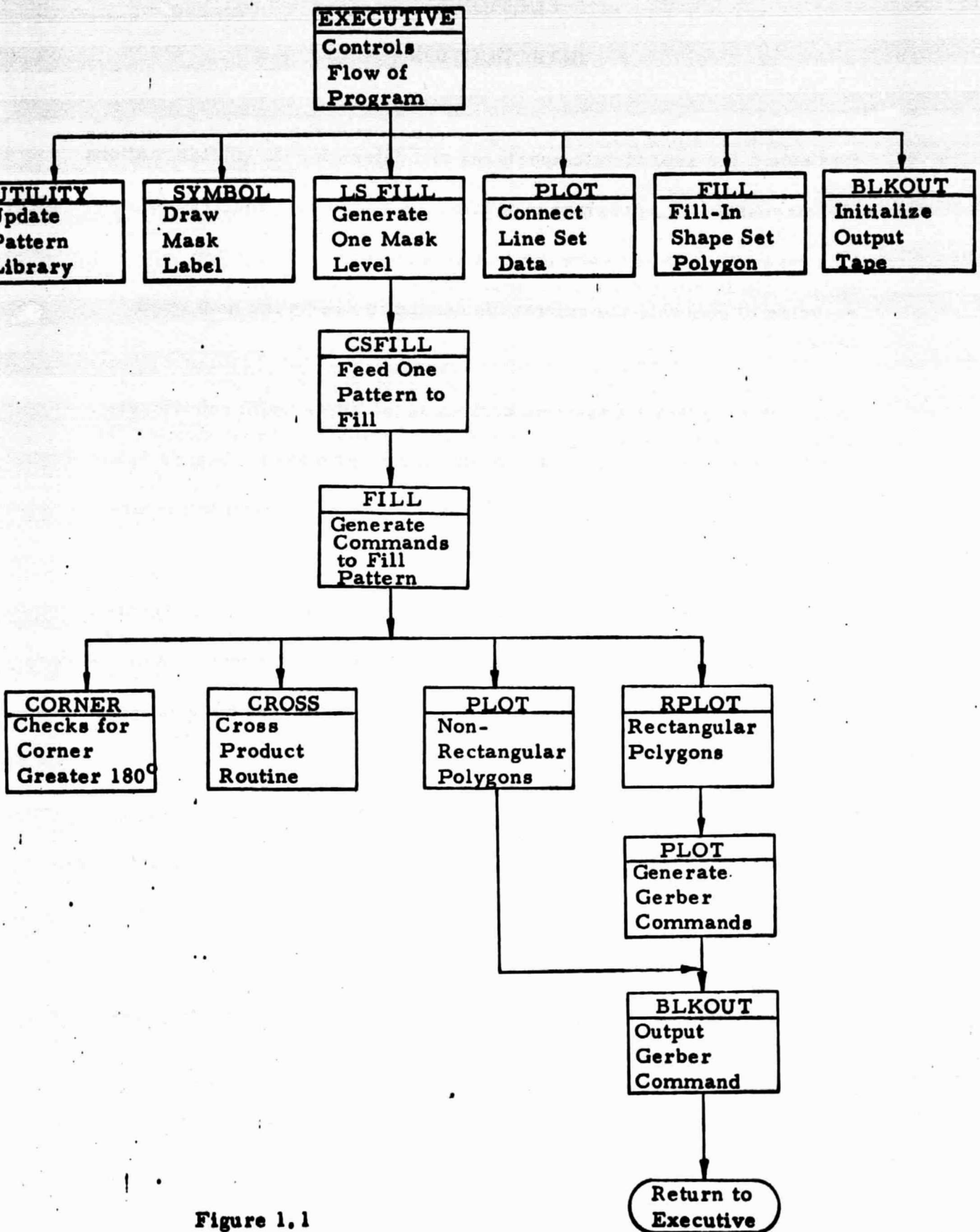


Figure 1.1

- Place the component pattern at the specified location and orientation on the chip;
- Create the Gerber commands to completely expose or "fill-in" every polygon;
- Draw the interconnect lines if line set data is specified;
- Draw the scribe lines around the chip as specified by the shape set data;
- Label the created mask as specified by the symbol data.

After the above processing has been completed for each mask level, the Artwork Program terminates.

Many of the subroutines in the Artwork Program are small and can be adequately described by a one-page functional flowchart. These subroutines are illustrated in Figures 1.2 through 1.9. These flowcharts and the comments incorporated into the program listing should provide a sufficient explanation of the functions performed by the subroutines.

Special sections have been included in this report to describe the more complicated algorithms used by the FILL subroutine and the UPDATE subroutine. The major portion of the logic required to fill-in the polygons of a given mask level is concentrated in the fill subroutine and the special plot options subroutines. Sections IV and V contain both detailed discussions and detailed flowcharts of the operations required to generate the Gerber commands necessary to produce the final artwork output.

Section II describes the format of the binary pattern library used by the Artwork Program. Any modifications to the format of this library will effect several subroutines, and therefore, care should be taken to insure that proper control is maintained over the format of the library.

Section III describes the format of the various arrays used to store, format, and manipulate the components and pattern sets used to create the artwork of each mask level of a chip. To understand the operations performed by the Artwork Program, it is imperative that the programmer become familiar with these arrays.

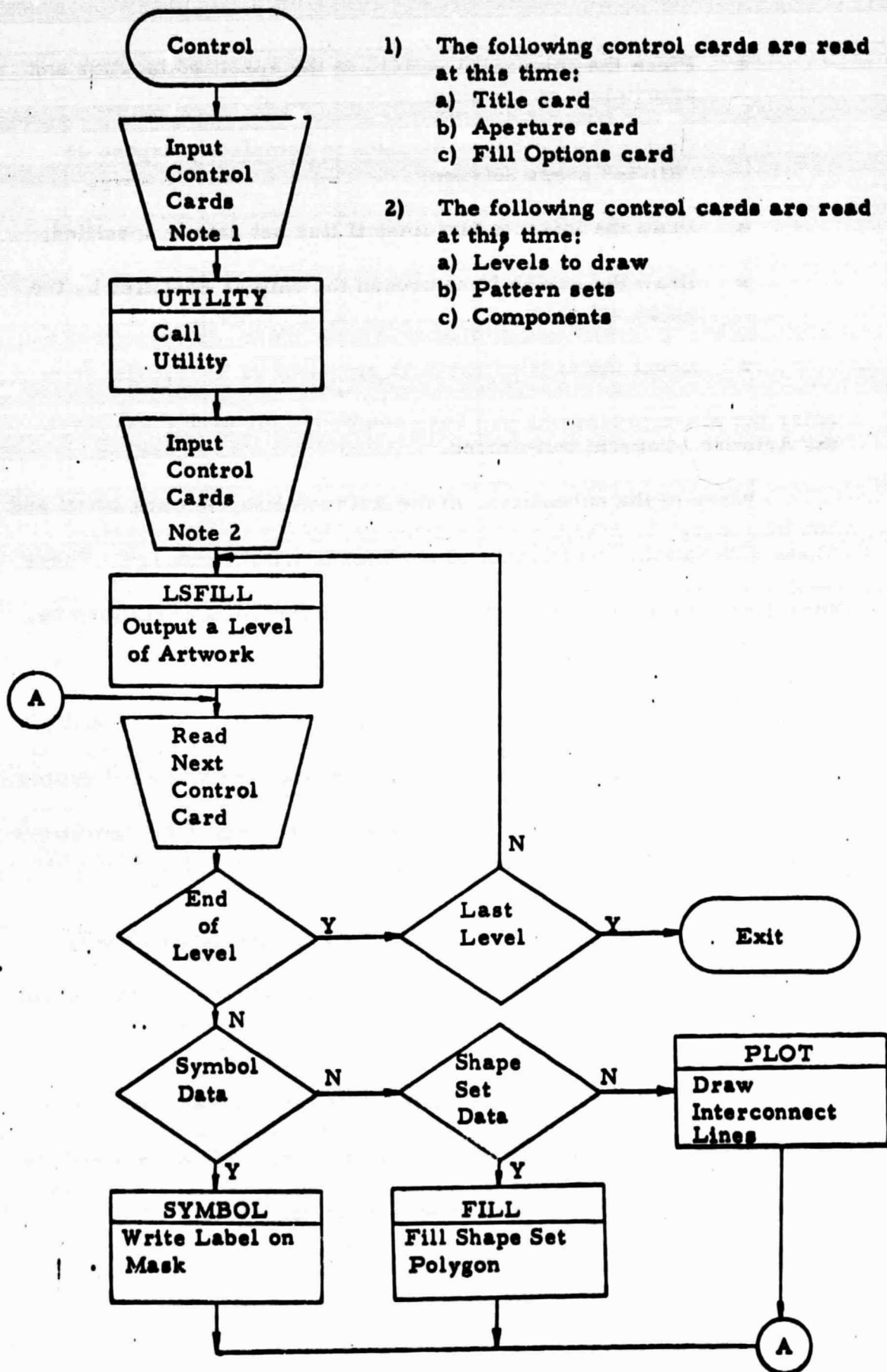


Figure 1.2

LSFILL SUBROUTINE

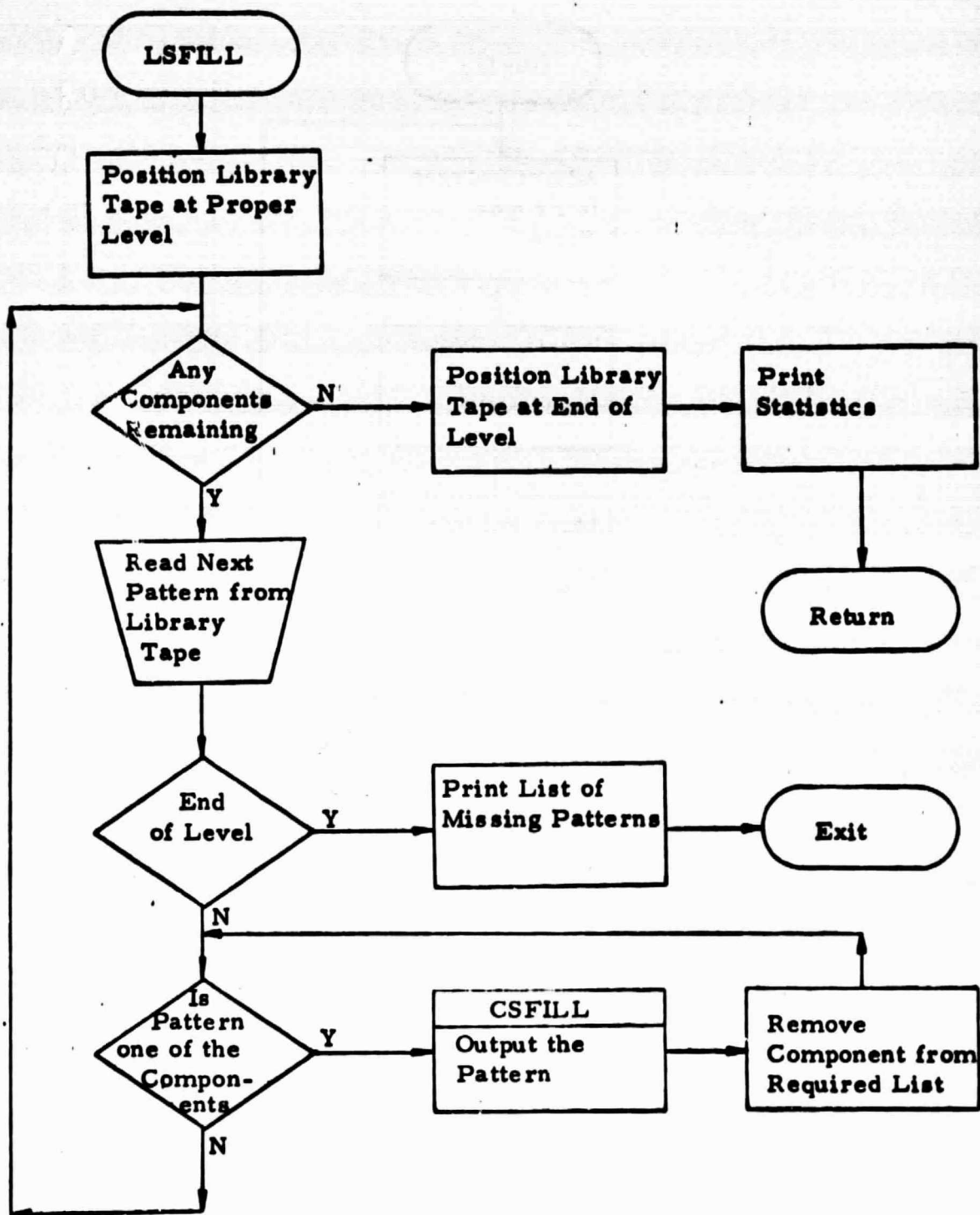


Figure 1.3

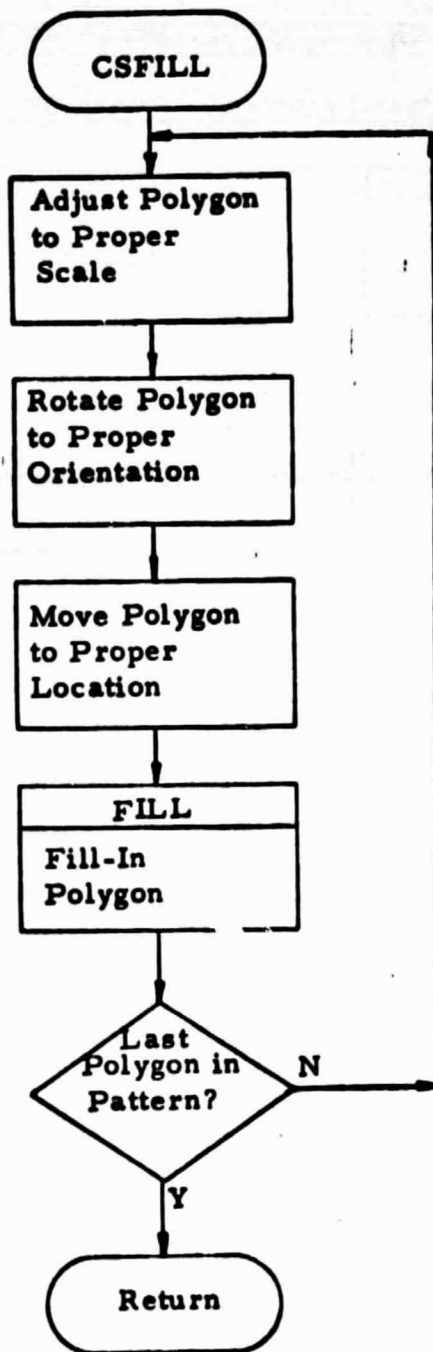


Figure 1.4

PLOT SUBROUTINE

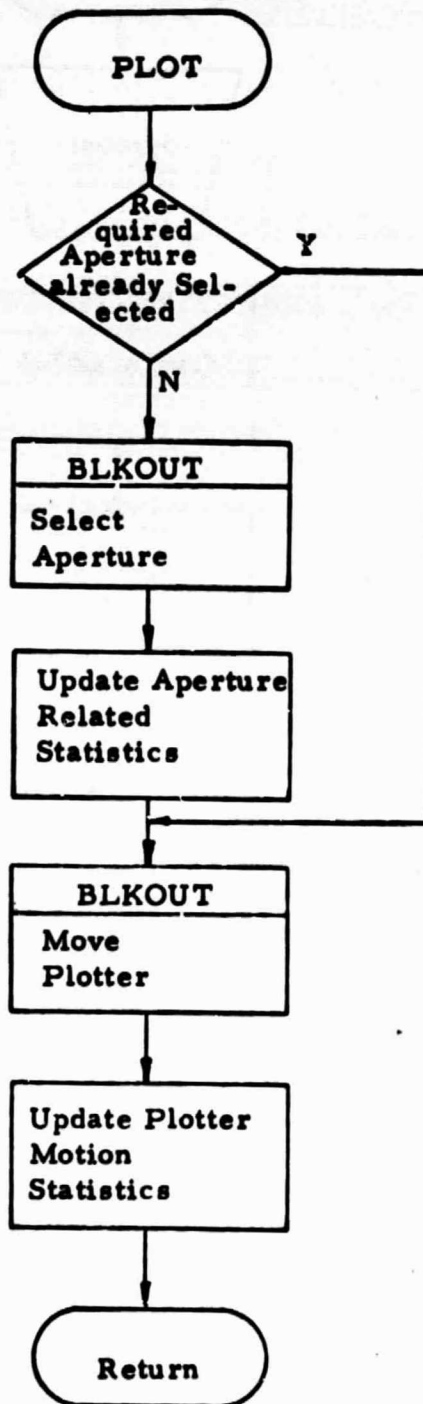


Figure 1.5

SYMBOL SUBROUTINE

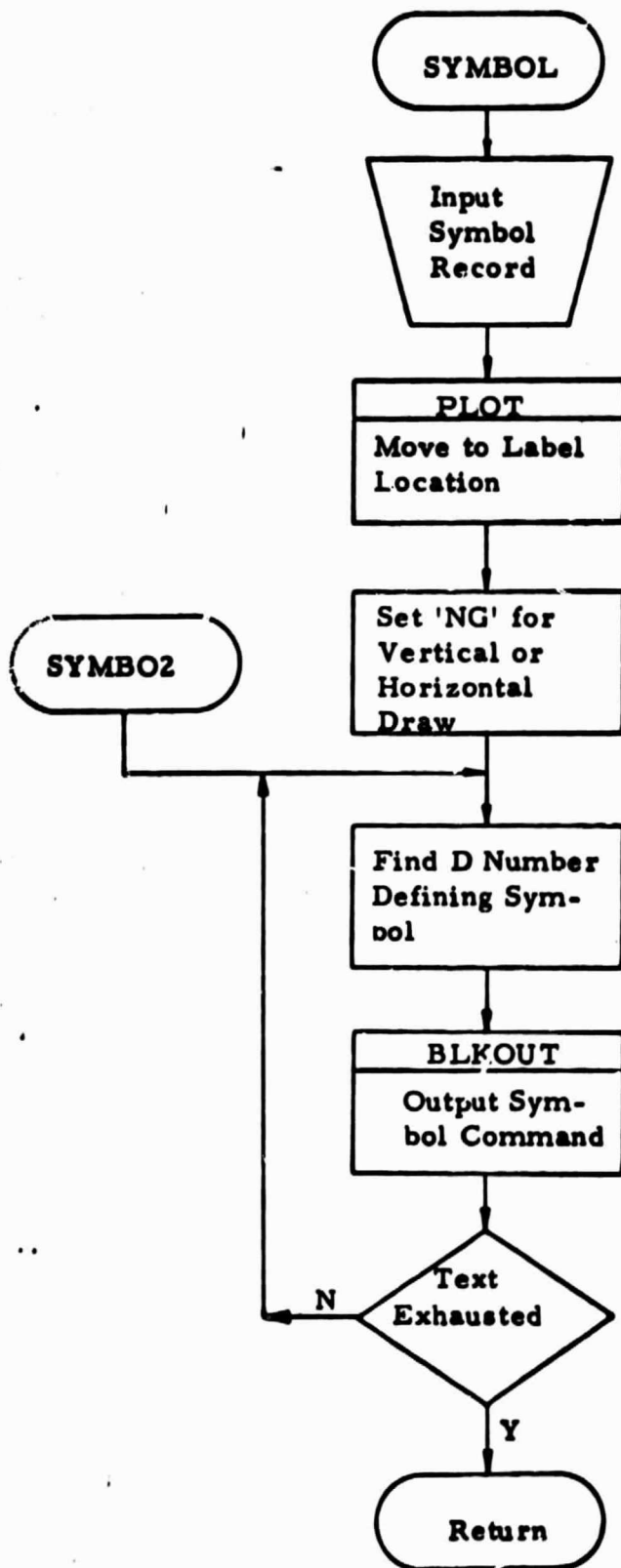


Figure 1.6

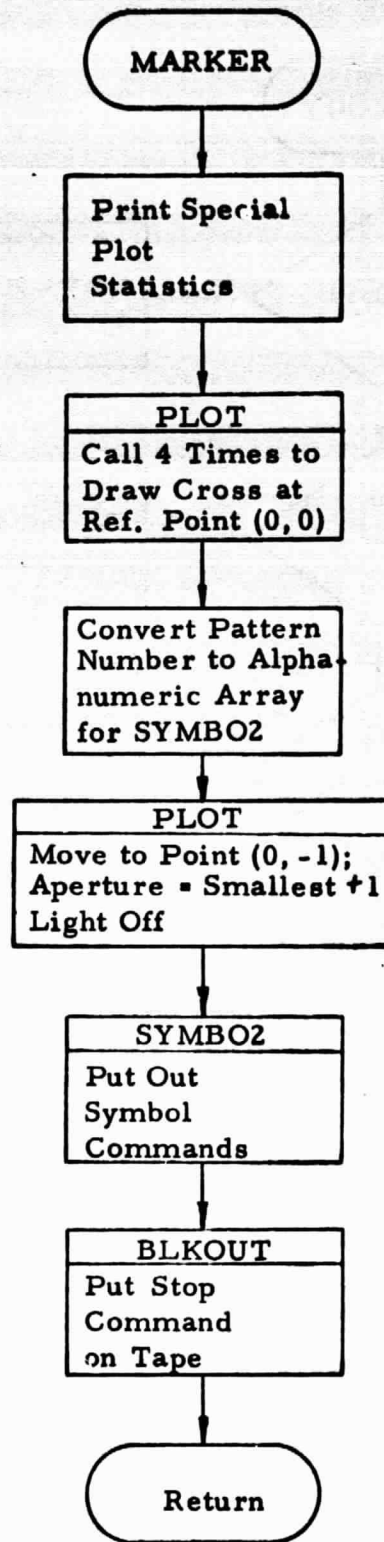


Figure 1.7

BLKOUT SUBROUTINE

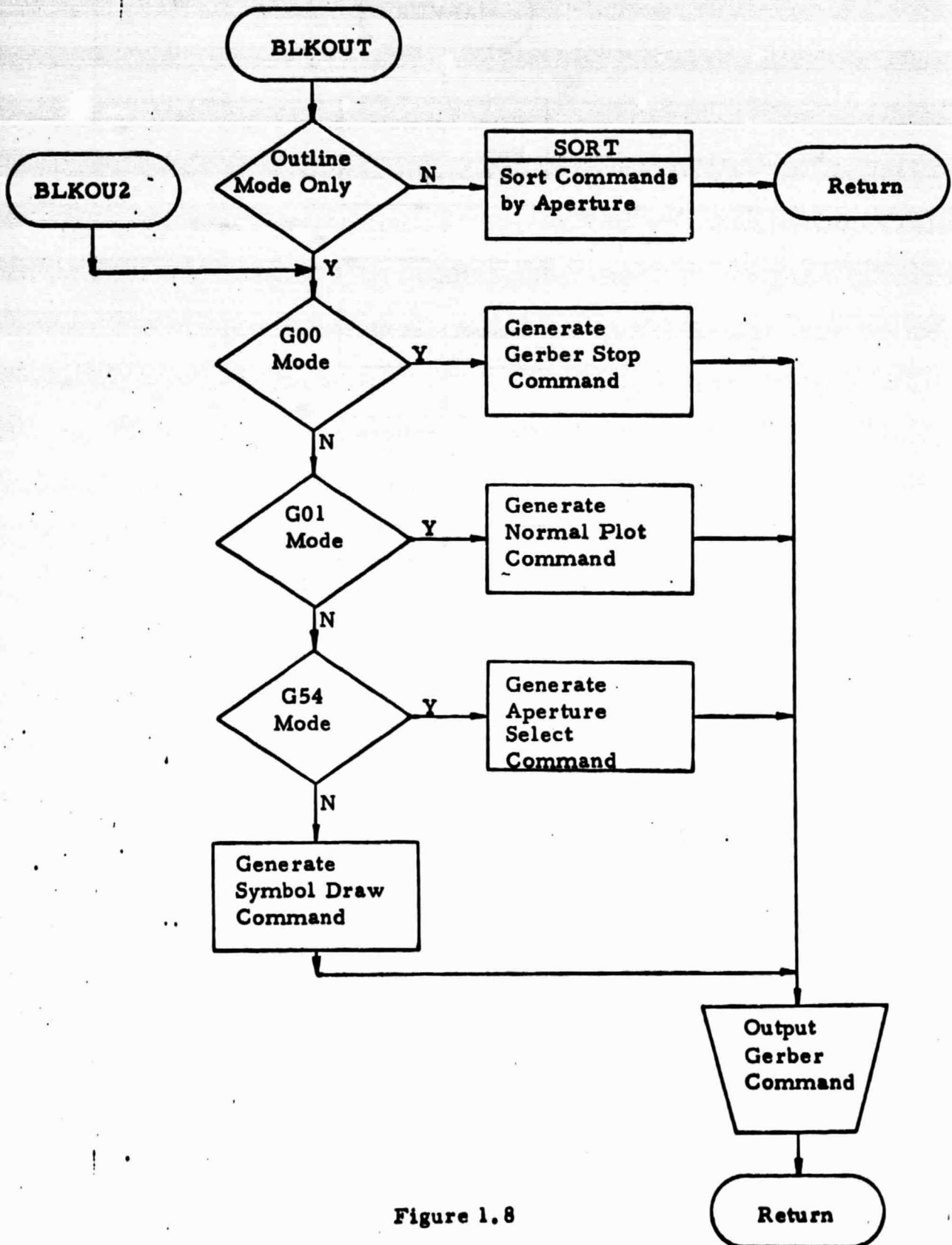


Figure 1.8

APERTURE SORT SUBROUTINE

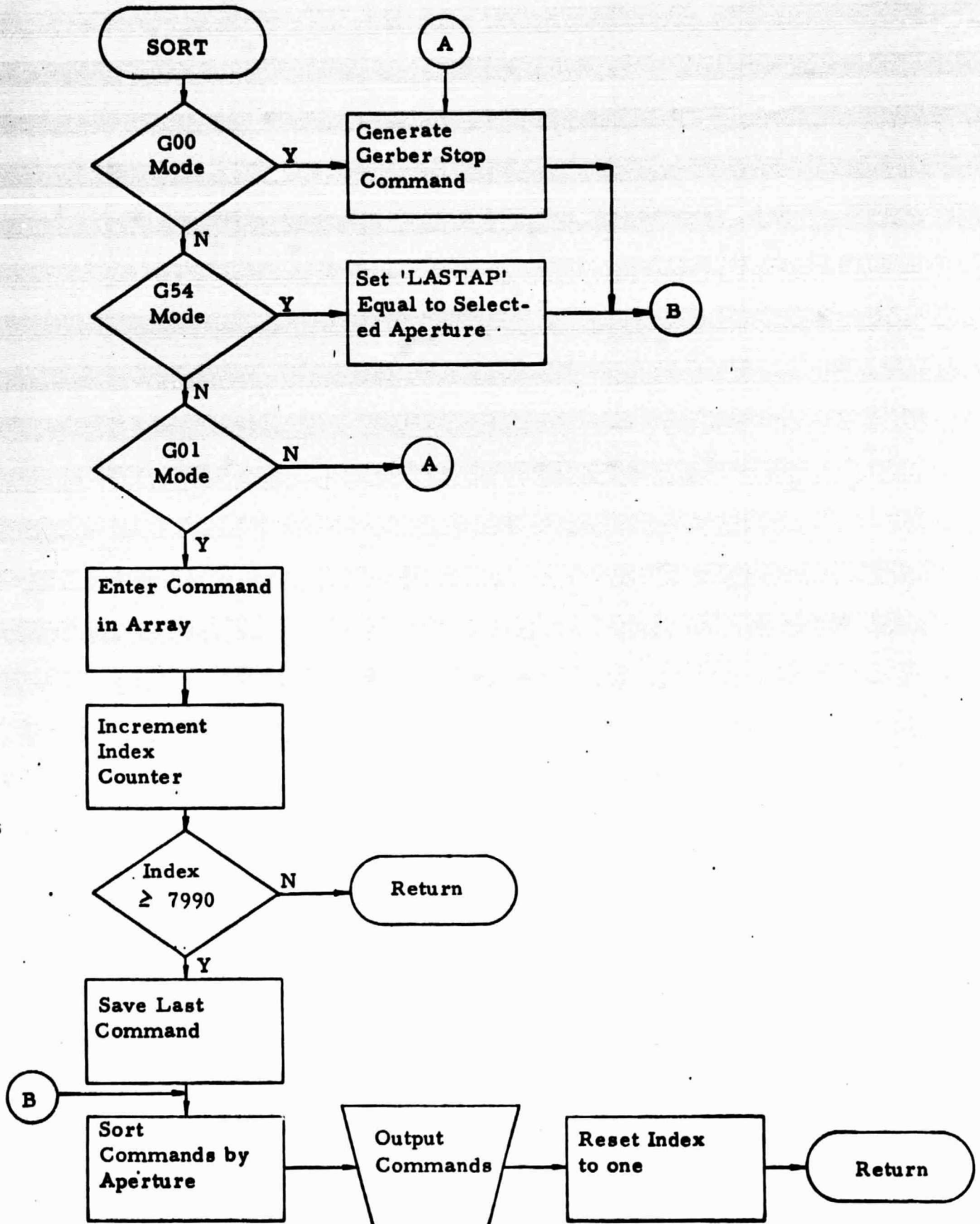


Figure 1.9

SECTION II

BINARY PATTERN LIBRARY

Within the Banning System, the term pattern is used to identify the polygon or set of polygons defining the artwork required to construct a given mask. Therefore, the Banning Pattern Library may be defined as the collection of polygons defining the artwork required to construct each mask of every standard Banning cell. In order to understand the method in which the Artwork Program processes the pattern definitions, it is important to understand the arrangement of patterns within the Pattern Library.

Since the Artwork Program produces the output artwork commands for one mask level at a time, the pattern library has been formatted into levels where each level contains all of the patterns defining the particular mask level of each standard Banning cell. The Artwork Program is capable of supporting up to nine levels of circuit masks, and therefore the pattern library can theoretically be divided into nine major sections. However, there are presently only six levels defined within the Banning system, resulting in the following divisions in the pattern library:

- LEVEL 1 - P-REGION
- LEVEL 2 - CONTACT & GATE
- LEVEL 3 - CONTACT
- LEVEL 4 - METAL
- LEVEL 5 - SAME AS LEVEL 2 (DEEP DIFFUSION)
- LEVEL 6 - PROTECTIVE COVERING

This multi-level division of the pattern library assumes that each standard Banning Cell has a particular design for each mask level. However, there are Banning cells that appear on only one level mask or appear on every level, but use the same shape on each level. In order to facilitate the definition of cells of this type, the following numbering scheme was developed:

- 0000-9999: All Banning cells must be assigned a number within this range.
- 0000-8999: Banning cells with numbers within this range will be considered Family Patterns. That is each cell

will be assigned a number with the units digit equal to zero and be broken down into mask levels with the value of the units digit specifying the level. For example, the Banning 2 Input Nor cell is defined as a family pattern and referred to as cell number 2070. The cell contains a unique pattern for each level mask with each level indicated by the unit digit of the number: 2071 for level one, 2072 for the level 2, etc.

- 9000-9599: Banning cells with numbers within this range are considered One-Level Patterns. Each cell will consist of only one pattern definition which is included in the pattern library at the level indicated by the units digit of the number assigned to the cell. For example, cell number 9034 refers to a Banning Pad that consists of one pattern on the fourth level of the pattern library.
- 9599-9999: Banning cells with numbers within this range are considered All-Level-Patterns. Each cell will consist of only one pattern definition, but it will be included on each level of the pattern library. The units digit has no significance for All-Level-Patterns. An off-chip alignment mark is a good example of an all-level-pattern.

Figure 2.1 illustrates the format of the pattern library. With this arrangement of patterns, the Artwork Program can position the library tape at the level being processed and have immediate access to all predefined patterns. The family-pattern concept is the most important and includes the majority of the patterns encountered. Family-patterns are specified to the Artwork Program by number, for example 2070, to be drawn at a desired location with a specified orientation. The Artwork Program then places pattern 2071 at this location for level 1 of the artwork, pattern 2072 for level 2 of the artwork, etc., continuing to the last level.

Table 2.1 illustrates the format of a level of the binary pattern library. This format is repeated for every level of the library. A two-word record of the following format terminates the library:

ENDLIB

BANNING PATTERN LIBRARY

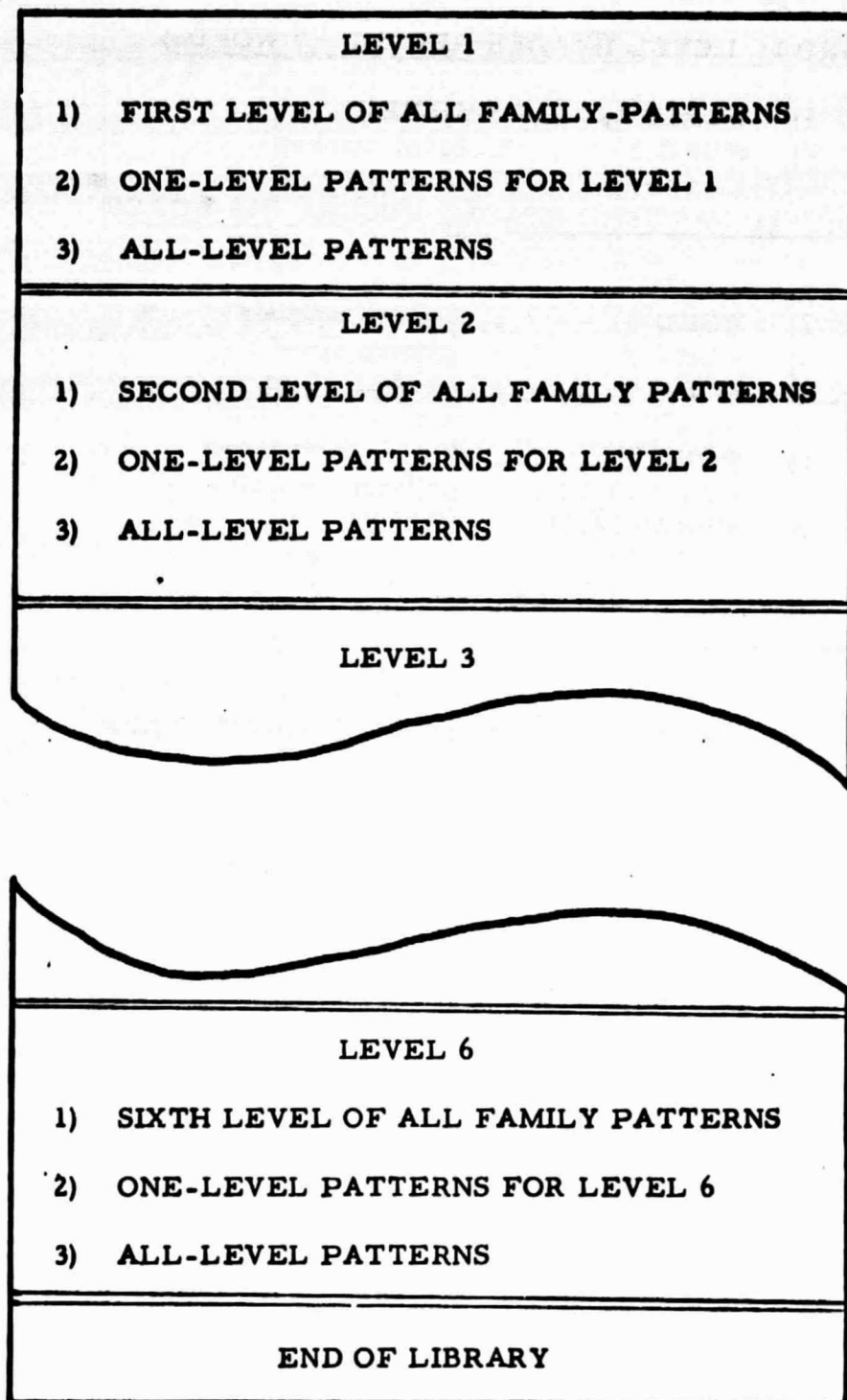


Figure 2.1

FORMAT OF THE BINARY PATTERN LIBRARY

RECORD 1: LEVEL HEADER RECORD (3 WORDS)

- 1) WORDS 1,2 : 'LEVEL'
- 2) WORD 3 : level number

RECORD 2: PATTERN HEADER RECORD (16 WORDS)

- 1) WORDS 1,2 : blanks
- 2) WORD 3 : pattern number
- 3) WORD 4 : pattern scale
- 4) WORD 5 : number of words in vertex record
- 5) WORD 6 : X reference point
- 6) WORD 7 : Y reference point
- 7) WORDS 8-13 : pattern identification
- 8) WORDS 14, 15 : 'POLY'
- 9) WORD 16 : number of polygons in vertex record

RECORD 3: VERTEX RECORD (MAXIMUM OF 2,000 WORDS)

- 1) WORD 1 : number of sides of first polygon
- 2) WORDS 2-n : vertices of first polygon

. . .
definition of remaining polygons
. . .

RECORD 4: END LEVEL RECORD (16 WORDS)

- 1) WORDS 1,2 : 'ENDLEV'
- 2) WORDS 3-16 : blanks

Table 2.1

SECTION III

KEY ARRAYS IN THE ARTWORK PROGRAM

A group of key arrays, set up in the main program, governs the placing of patterns from the library tape. A brief description of each array is given below.

NDIR
Index to NPATM array. Plus value denotes standard pattern. Zero means pattern has been put out. Minus denotes pattern set.

Size limit is 500.

NPATM	NPTATM	PATXM	PATYM
Component number to be placed.	Orientation of component. If component is a pattern set, the value, excluding units digit, is the index of pattern set in NPS array.	Gives the X and Y locations at which patterns and pattern sets are to be placed.	

Size limit is 500.

NPSA	NPSTAT	PSAX	PSAY
Pattern numbers in pattern set.	Orientation of patterns in pattern sets plus one. Made negative where pattern is outputted for each level.	Location to place pattern in pattern set.	

Size limit is 500.

NPS	NPPS	NPSDIR
Component number of pattern set.	Number of patterns in set.	Index of start of pattern set in NPSA.

Size limit is 50.

The NDIR and NPSTAT arrays are set up for each level in the main program. When a pattern is read from the library tape by LSFILL, NDIR is scanned and used as an index to NPATM. In the case of simple patterns, this determines if and where the pattern should be placed. After placing, the NDIR entry is set to zero. For pattern sets, the absolute value of the negative entry in NDIR indexes the pattern set in NPATM. The NPATM entry in this case, when divided by 10, gives the index of the pattern set in NPS. The corresponding NPPS and NPSDIR entries give the range and index of the patterns in the pattern set for the NPSA array. When a pattern in a pattern set is output, the number in NPSTAT is set to a negative value. When all the orientations in NPSTAT are negative, the entry in NDIR is set to zero. Before the next pattern is read from the library tape, NDIR is shortened by eliminating the zero entries.

SECTION IV

OUTLINE AND FILL SUBROUTINE

The following paragraphs, together with the flowcharts and commented listing, are intended to be a detailed explanation of the outline and fill subroutine, hereafter referred to as "FILL." The supporting subroutines, CROSS, CORNER, and RPLOT, are also described in order to present a total picture of the functions performed by the fill-in subroutine.

The FILL subroutine can be best described by orienting the discussion toward the five major functions performed by the subroutine: SEQUENCE DETECTOR, SHRINKER, REJECTOR, SMASHER, FILL-IN.

4.1 INPUT DATA

Input data are supplied to FILL through common. The common variables that must be set prior to calling FILL are:

SOVLP	Slit overlap constant, set to 0.001 by the main program.
KSMA KOUTL KFSMA	Smash, outline, and fill-smash option keys.
XB YB	Coordinates of polygon vertices. The first point need not be repeated.
NSIDES	The number of sides of the input polygon.
BORMAX	The width of the border desired on the polygon outline. If set to zero, the outline is generated with the smallest round aperture.
NLR	The number of round apertures available for drawing lines. NLR must not exceed 18.
SIZLR	A list of the sizes of round apertures available. The sizes must appear in the SIZLR array in ascending order.

NAPLR	A corresponding list of Gerber D-numbers for the sizes in the SIZLR array.
NSQ	The number of available horizontal slit apertures. This must be the same as the number of available vertical slit apertures. NSQ must not exceed 9. It may be set to zero, in which case no slit apertures will be used.
SIZQH NAPQH	Arrays of horizontal slit sizes and D-numbers arranged in ascending order by size.
SIZQV NAPQV	Similar arrays for vertical slits. Vertical slits have their longest dimension in the Y-direction.
NFIRST	The array subscript for the smallest desired round aperture. This is usually one, but can be set to larger integers if high accuracy is not required on outlines.

4.2 SEQUENCE DETECTOR

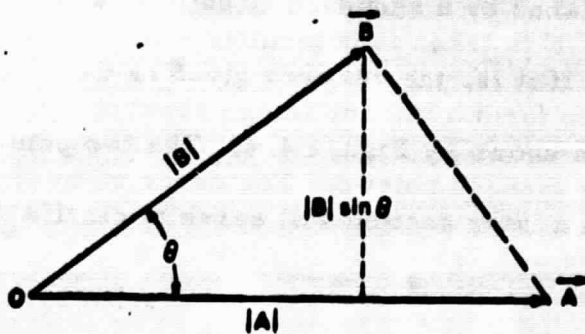
Polygons used as input to FILL must have no more than 200 sides and the number of interior angles larger than 180 degrees (reentrant angles) must not exceed 100. An input polygon must not intersect itself; it must not look like a figure eight; and it must not have three successive points in a straight line. It must be large enough so that after it is shrunk by the radius of the smallest aperture to be used it will not intersect itself.

The purpose of the sequence detector is to assure that the coordinates of the polygon vertices stored in XB and YB are in a clockwise sequence. If the sequence is known to be clockwise, it is a simple matter to determine whether a particular angle is reentrant.

The quantity QB is used as a summing variable to sum cross products of vectors with ends XB and YB. The final QB is twice the area of the polygon, as shown by Figures 4.1 and 4.2. A negative area implies that the sequence is clockwise. A positive area causes the sequence of vertices to be reversed.

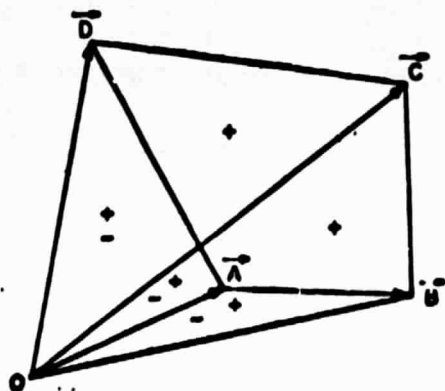
4.3 SHRINKER

SHRINKER receives and changes the vertex information stored in XB and YB to produce a new polygon with vertices moved inward along angle bisectors in a distance such that the new sides are half



$$\begin{aligned}\vec{A} \times \vec{B} &= |\vec{A}| \cdot |\vec{B}| \sin \theta \\ &= 2 \text{ area of } \triangle OAB\end{aligned}$$

Figure 4.1 Area of Triangle



$$\begin{aligned}\vec{A} \times \vec{B} + \vec{B} \times \vec{C} + \vec{C} \times \vec{D} + \vec{D} \times \vec{A} \\ = 2 \text{ area of } ABCD\end{aligned}$$

Figure 4.2 Sequence Detector

the diameter of the smallest aperture inside the original sides. An example of a shrunken polygon is shown by Figure 4.3

Shrinking is accomplished by a sequence of calls to subroutine CORNER. A cross product QE is taken to determine whether a given vertex is a reentrant angle. If it is, the vertices given as CORNER arguments must be changed to form a mirror image about the vertex before CORNER is called, as shown by Figure 4.4. The two points A' and B' are mirror images through point O. The description of subroutine CORNER given in a later section will serve to clarify this.

4.4 REJECTOR

The purpose of the REJECTOR part of the program is to check a shrunken polygon to see if it intersects itself. Bad input data for polygons are thus found and print-outs are made to describe possible error points in the polygon. The possibility of an illegal polygon's being processed by the FILL program is thus avoided. Such an illegal polygon would cause an error which might require the computer to stop. A knowledge of the inputs and operations of subroutine CROSS, which is documented in a later paragraph, is useful in understanding this test.

4.5 SMASHER

The SMASHER part of the program breaks up a legal polygon stored in XB and YB to produce a number of smaller polygons in XA and YA so that none has a reentrant angle. This is accomplished by "cutting" or breaking up polygons at the reentrant vertices until all reentrant vertices have been eliminated.

It will be important in following this section to know how groups of polygons are stored in XA and YA. Comments supplied in the listing explain the variables used to store groups of polygons.

The KSMA option key is sensed in this part of the program. The smash line referred to in the comments is the line of the "cut" used to remove a reentrant angle. This line must be through the reentrant vertex and can be either the bisector of the reentrant angle or an extension of one of the reentrant angle sides, depending on the value of KSMA. When dealing with polygons made mostly of horizontal and vertical lines, it is useful to have smash lines that are extensions of reentrant angle sides, so that no unnecessary diagonal lines are added to intermediate stages of the artwork.

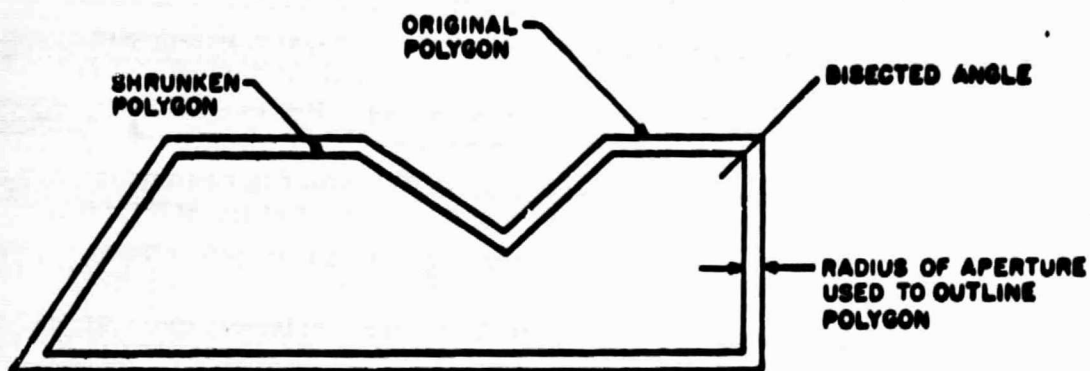


Figure 4.3 Shriner Program

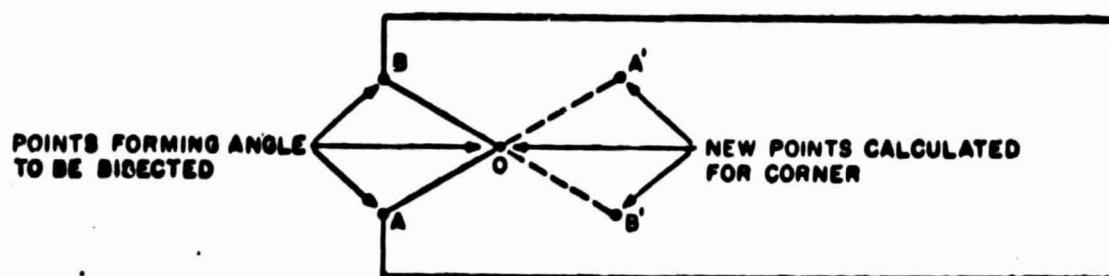


Figure 4.4 Shrinking at Reentrant Angles

4.6 FILL-IN

This part of the program determines the actual plotter motions needed to fill in, one at a time, the convex polygons stored in XA and YA. If slit apertures are available, each polygon is first tested to see if it is a rectangle and vertical and horizontal sides. Rectangles are filled in by setting upper and lower X and Y boundaries and calling RPLLOT, which generates the short sequence of movements needed to fill in the rectangle. If a polygon is not a rectangle and if the KFSMA (secondary smash) option has been specified, the program will check the polygon in an attempt to find three successive sides that are either horizontal or vertical. If the polygon satisfies this condition, part of the polygon is filled with slits by calling RPLLOT. The remainder of the polygon is then returned to XA and YA for further tests. The outline option, KOUTL, applies in any case where RPLLOT is used to fill all or part of a polygon. Outlining of rectangular areas is generally done after RPLLOT is called, in case a condition exists which will make use of slits impossible. This would happen if a rectangle were too small to be filled by the available slits.

In the general case, where there are no suitable slit apertures available, a polygon is filled using round apertures. The largest aperture that will fit into the smallest internal angle without leaving a gap is chosen and used around the polygon. This process continues until a side becomes "over-run" and is eliminated, as shown by Figure 4.5. The process of filling and eliminating sides continues until the polygon is filled completely, or until the limit on the border, BORMAX, is reached. It will be necessary to study the commented program listing at the end of this report to acquire a full understanding of FILL-IN details.

A question might arise at comment 104 in the listing concerning formation of a triangle when sides (J, J+1) and (J+2, J+3) intersect on the "wrong" or "abnormal" side of the polygon. Figure 4.6 shows the "normal" orientation of the intersection point. In the normal case, side (J+1, J+2) is removed at this stage of the FILL program, but a special situation occurs when (J, J+1) and (J+2, J+3) intersect as shown in Figure 4.7. In this situation side (J+1, J+2) should not be removed. Instead, a triangle is formed from vertices J+1, J+2, and the intersection point. The triangle is a sufficient definition of the unfilled part of the original polygon. FILL-IN proceeds from there.

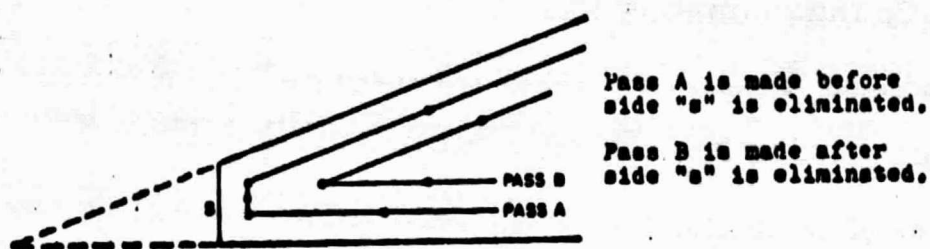


Figure 4.5 Side Elimination

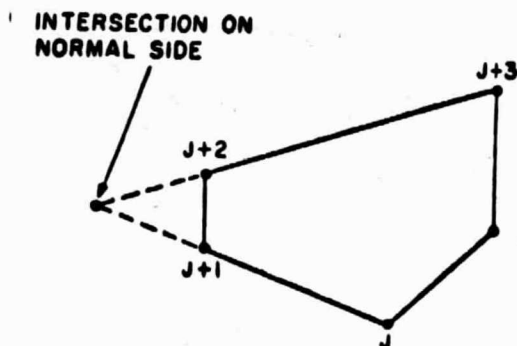


Figure 4.6 Normal Orientation of Intersection Point

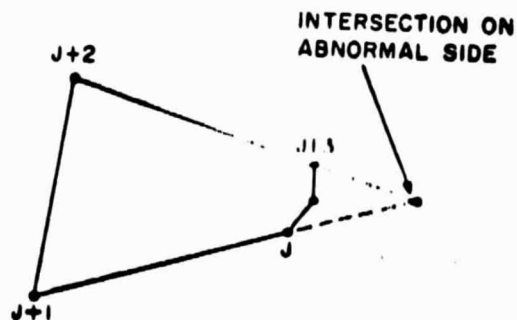


Figure 4.7 Abnormal Orientation of Intersection Point

4.7 AUXILIARY SUBROUTINES

Three other short subroutines are used by FILL. A description of each subroutine follows. Details can be easily obtained from the listing.

4.7.1 Subroutine CROSS

Given four points that define two straight lines, subroutine CROSS determines:

- If there is an intersection of the two lines;
- The intersection point;
- If the intersection point is on the second line segment.

If an intersection anywhere on the two lines is desired, PTS(12) is set to +1. If an intersection on the second line segment is desired, PTS(12) is set to -1. If no suitable intersection can be found, PTS(11) is set to -1 by the program. Otherwise it is +1 for a suitable intersection. Coincident lines are considered to have no intersection. The details of the subroutine are easily followed by a study of the program listing.

4.7.2 Subroutine CORNER

Given three points which describe an angle, subroutine CORNER determines the sine of the half angle and the plotting point (XVER, YVER) knowing the existing border width and selected aperture size. Figure 4.8 shows this point.

The subroutine first selects a point on the angle bisector by summing two unit vectors along the sides of the angle. The sine of the half angle is found by using the cross product of the unit vectors, and the point (XVER, YVER) is found by using a formula which is easily derived from Figure 4.8.

4.7.3 Subroutine RPLOTT

Given the X and Y coordinates of the boundaries for a rectangle, as shown by Figure 4.9, and a list of available slit apertures (their sizes and D-numbers), RPLOTT generates the Gerber Artwork Generator commands needed to fill in the rectangle.

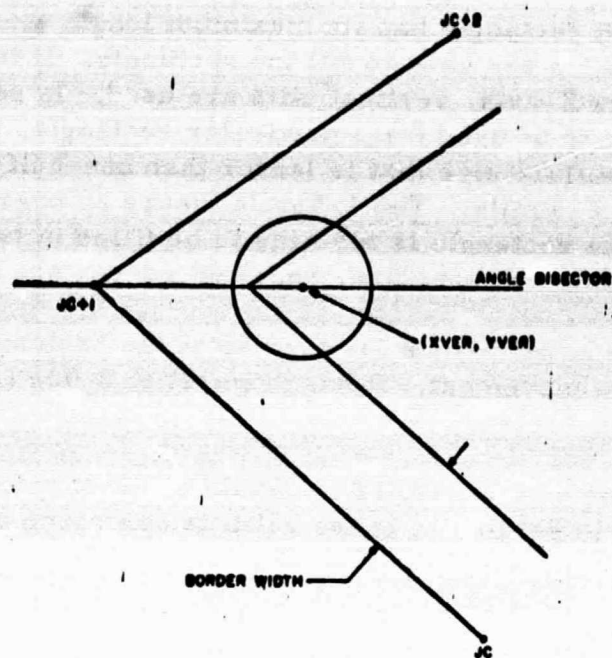


Figure 4.8 Determination of Plotting Point

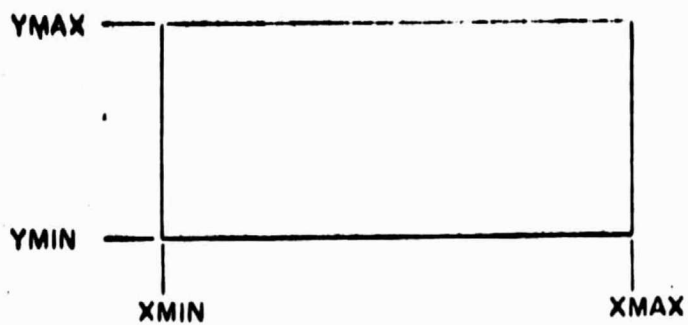


Figure 4.9 Rectangle Definition

REPRODUCIBILITY OF THE
ORIGINAL PAGE IS POOR

If the input rectangle has its maximum length along the Y-axis, horizontal slits are used to fill the rectangle. If the greatest length is along the X-axis, vertical slits are used. In selecting a slit aperture size to be used for a particular rectangle, the program picks the first aperture size that is larger than one-half of the rectangle width plus 1.5 mils. The 1.5 mils insure an overlap of the two slit passes. If the rectangle is too wide to be filled in two passes by the largest available slit aperture, repeated passes are made.

SOLVP is an allowance for overlap at the beginning and end of each slit aperture movement. It has been set to 0.001 (1 mil) with good results.

In any case where RPLOT is unable to fill a rectangle properly, the variable IGO is set to 1 to cause FILL to use round apertures on the rectangle.

4.8 OUTPUT

All of the tape output from subroutine FILL is made through subroutine PLOT. This subroutine performs many tasks independent of those required by FILL. For PLOT to produce valid Gerber commands, and to be compatible with FILL, it must have these capabilities:

- PLOT must obtain information about new plotter motions from X and Y in common and from its argument list;
- The first argument must be either 1 or 2, depending on whether the light is to be on or off during the motion;
- The second argument must be the aperture D-number. It may be zero for a light-off command.
- PLOT must sense a change in the aperture being used and must generate an aperture select command when such a change occurs.
- Each call to PLOT must generate a Gerber command (or two in the case that an aperture select is necessary) and either add the command to a buffer or write it on a tape.

For further details about the PLOT subroutine used for BANNING see the description of the other artwork routines.

4.9 FLOW CHARTS

The following pages constitute the flow charts for subroutine **FILL**. Flowcharts of the auxiliary routines were not included since they are short, and simple enough to be understandable from a description and the commented listing.

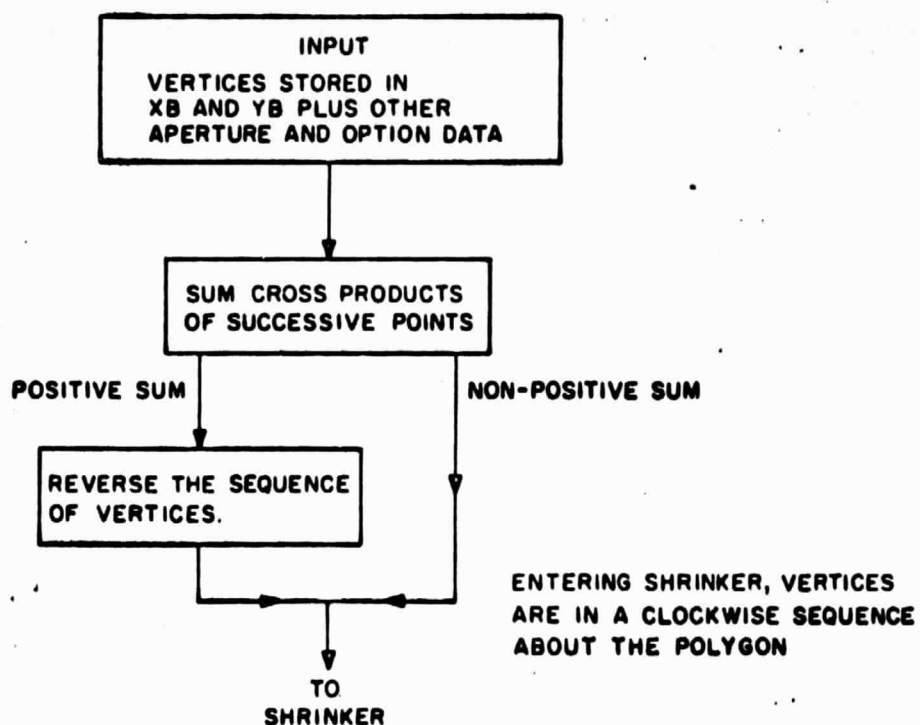
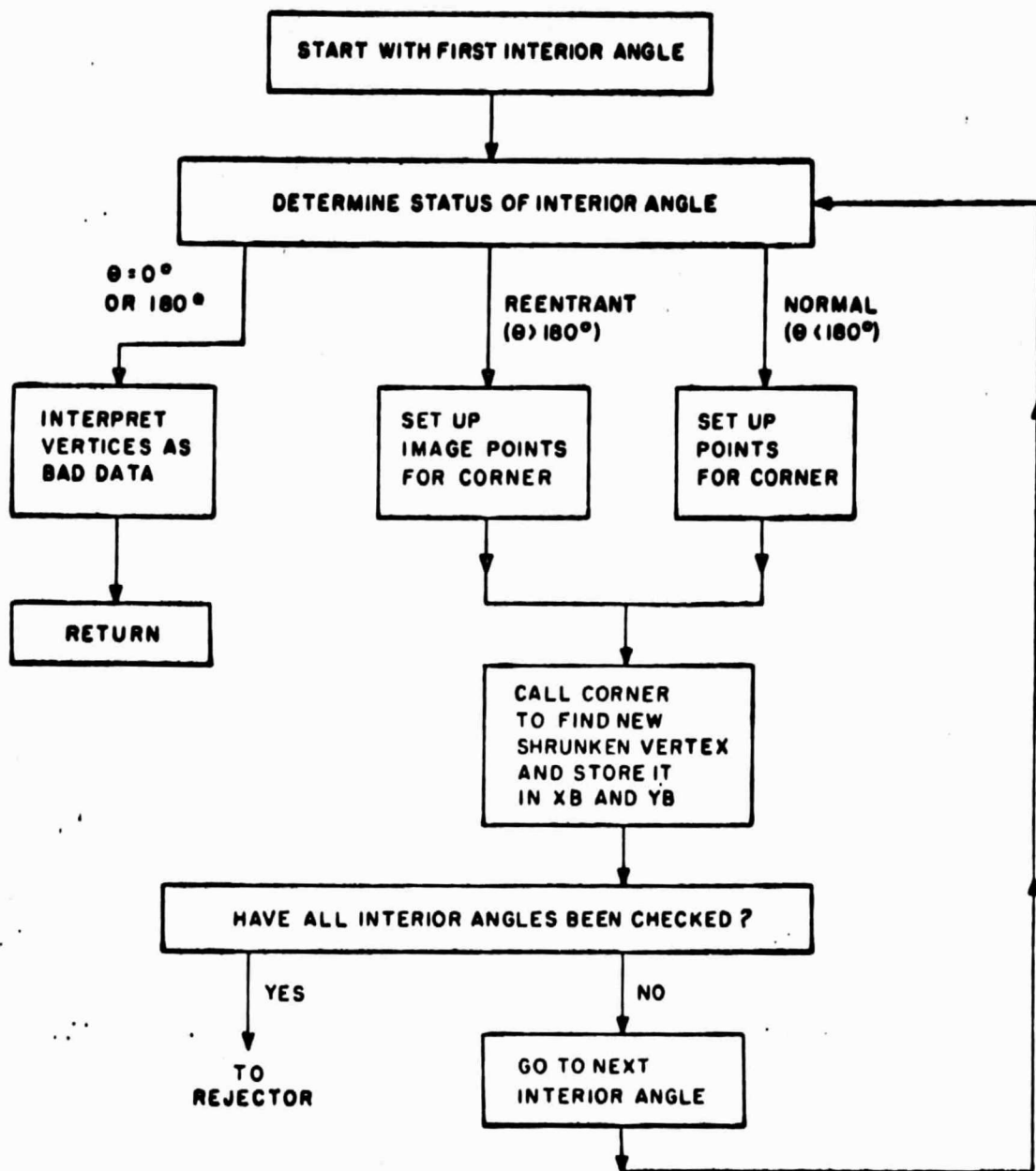
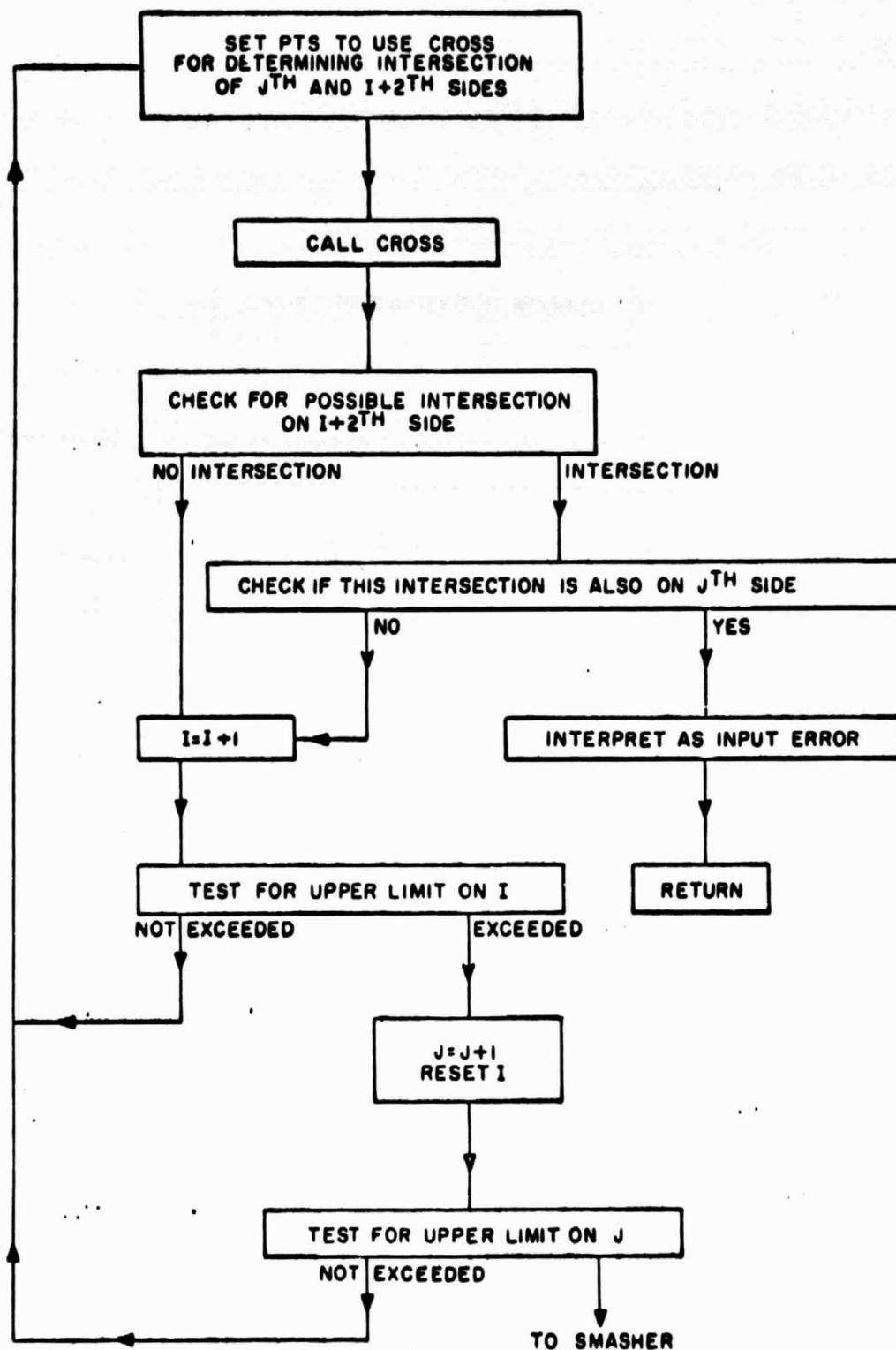


Figure 4.10 Sequence Detector



ENTERING REJECTOR, THE STORED VERTICES ARE THOSE OF A SHRUNKEN POLYGON CORRESPONDING TO THE STARTING POLYGON.

Figure 4.11 Shrinker

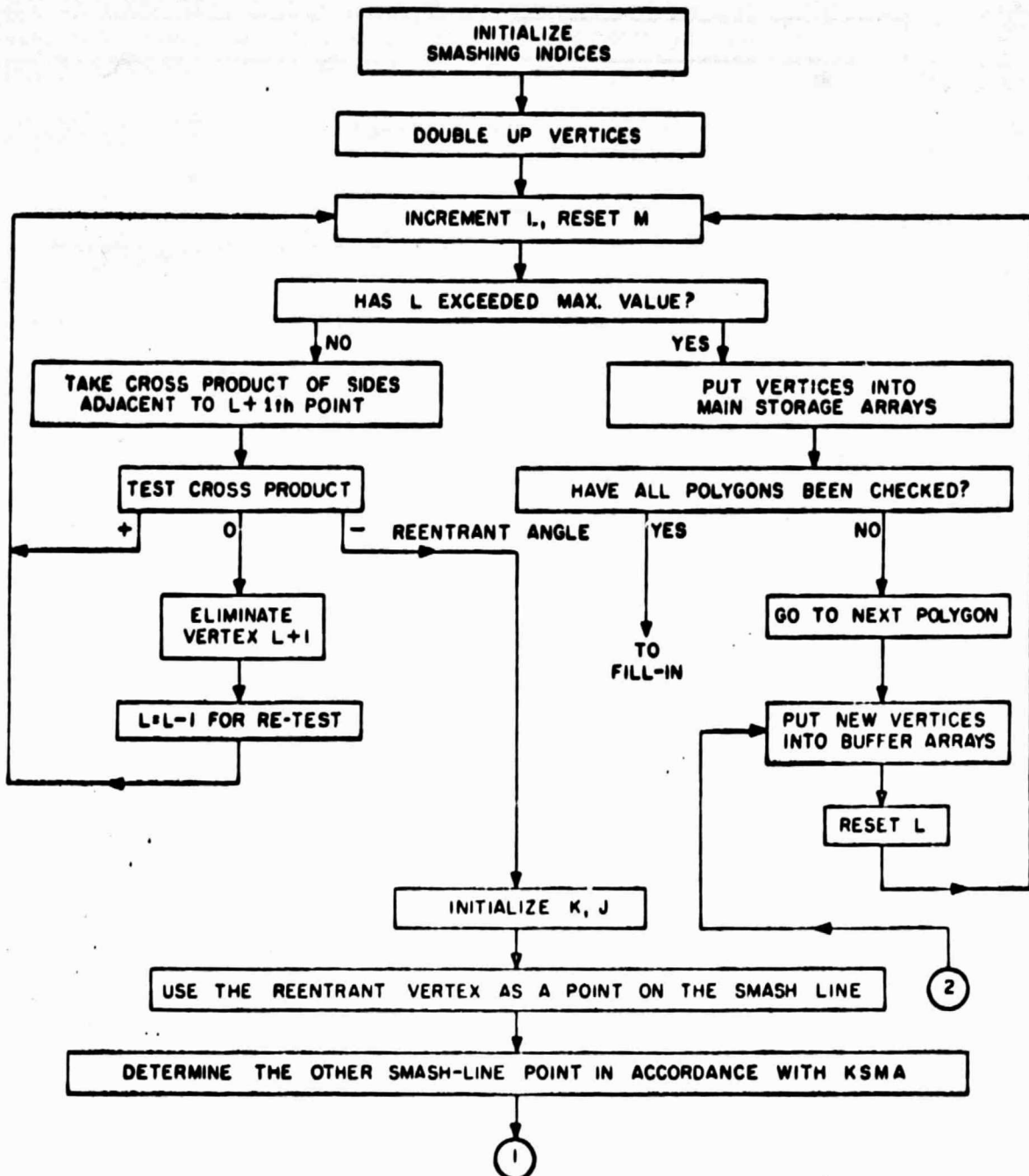


AS SMASHER IS ENTERED, POLYGON VERTICES ARE IN THE BUFFER STORAGE ARRAYS XB AND YB

Figure 4.12 Rejector

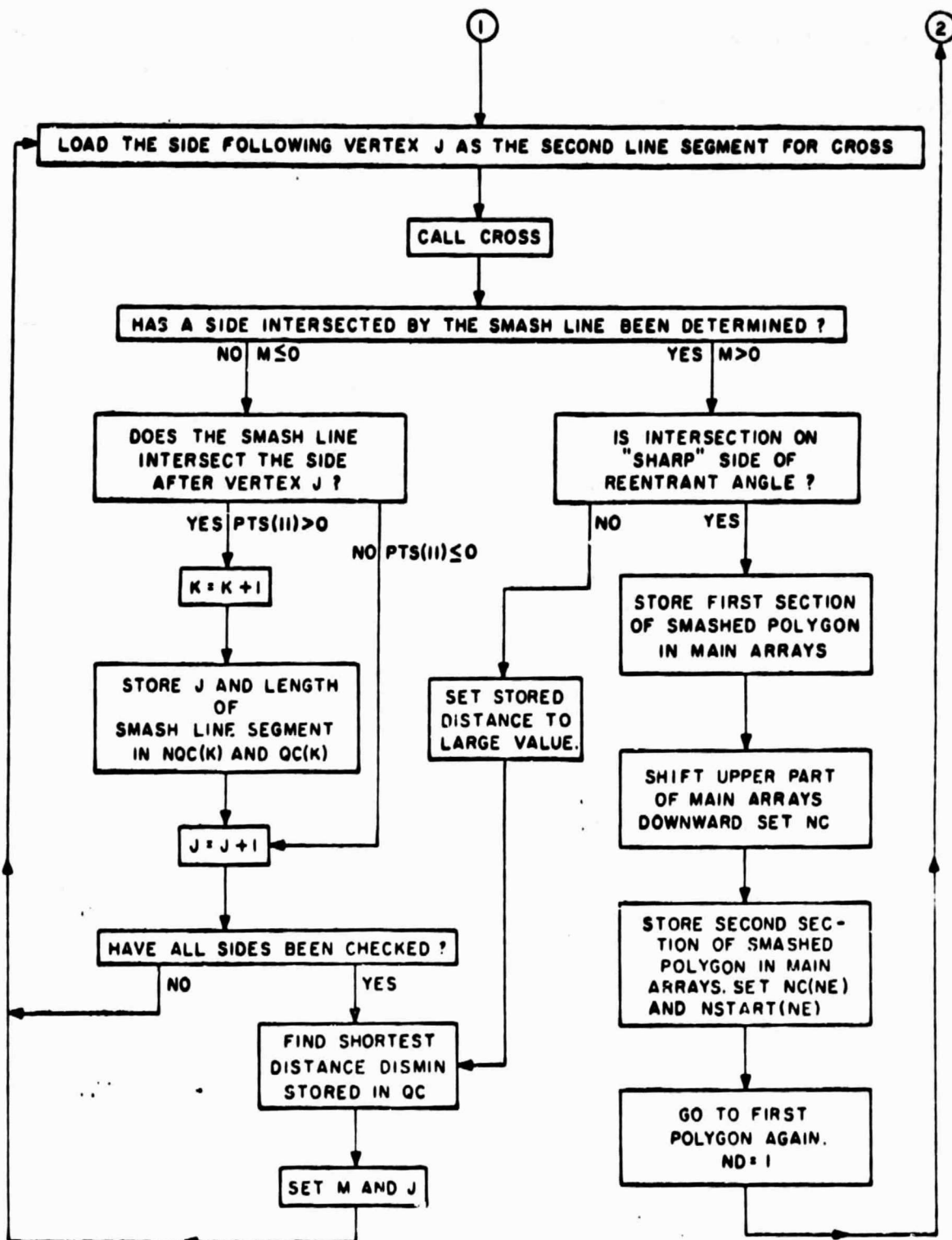
L = INDEX OF THE VERTEX BEFORE THE REENTRANT ANGLE

M = STARTING INDEX OF THE SIDE INTERSECTED BY THE SMASH LINE



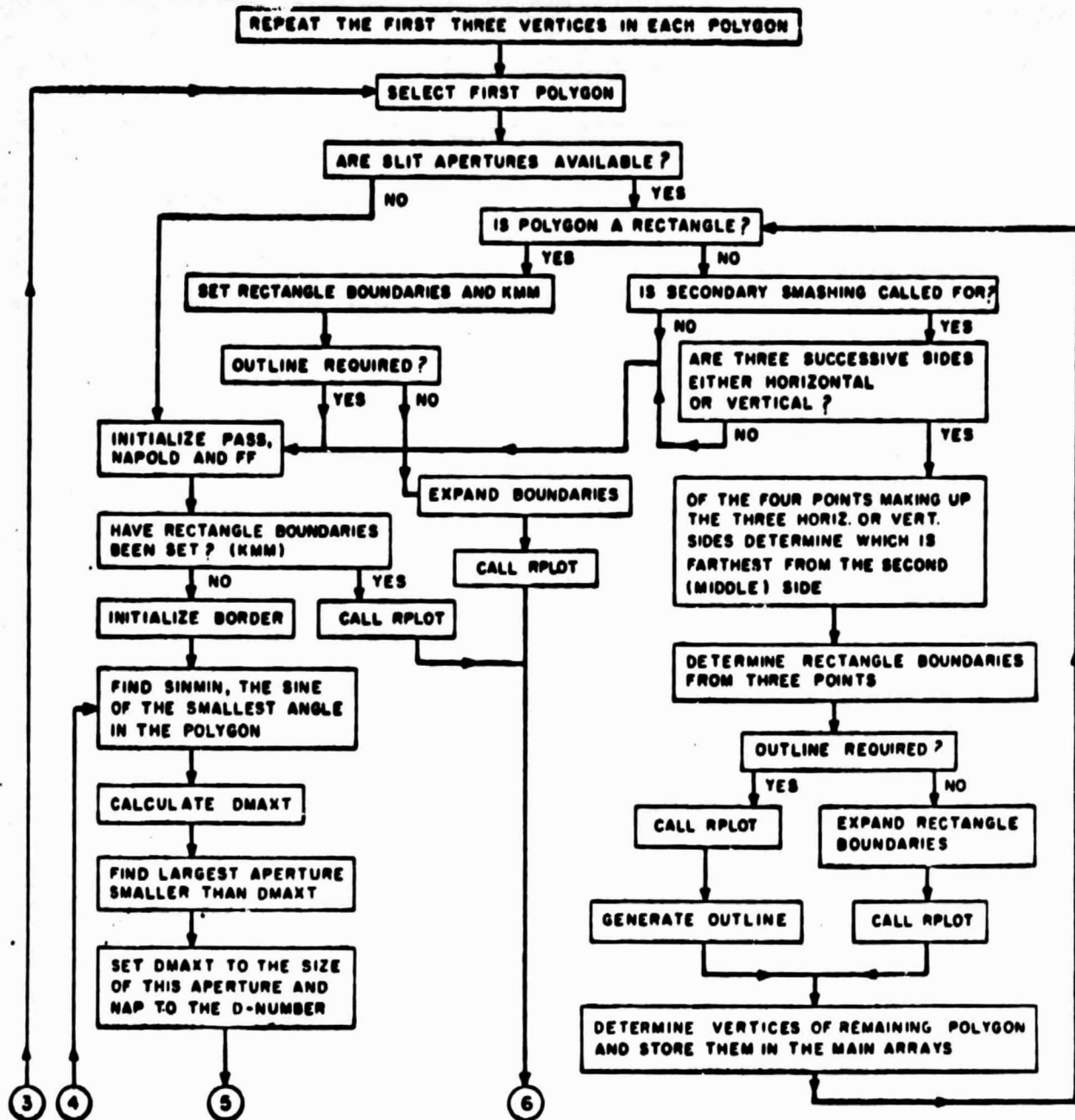
(CONTINUED ON NEXT PAGE)

Figure 4.13 Smasher



AS FILL-IN IS ENTERED THE MAIN ARRAYS CONTAIN NE CONVEX POLYGONS WHICH WILL BE FILLED ONE AT A TIME BY FILL-IN.

Figure 4.14 Smasher



(CONTINUED ON NEXT PAGE)

Figure 4.15 Fill-In

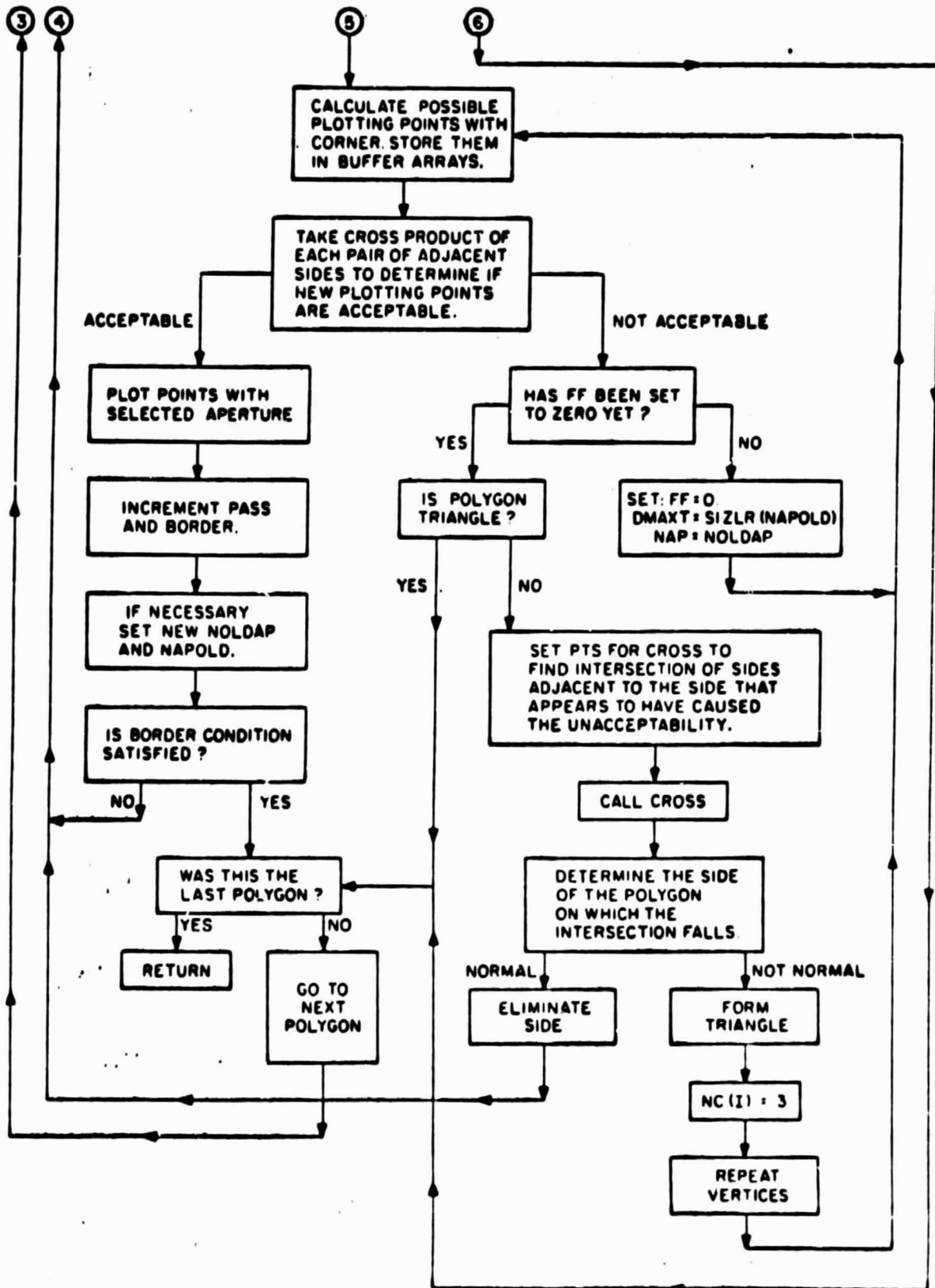


Figure 4.16 Fill-In

SECTION V

SPECIAL PLOT OPTIONS

Access to the Special Plot Options is made through the Utility Routine. There are five special plots that can be specified:

- 1) Dashed outlining,
- 2) Cross hatch,
- 3) Normal fill,
- 4) Outline only, and
- 5) Cross hatch.

Options 2 and 5 are identical, but the angle of inclination of the cross hatch lines may be positive for one and negative for the other, resulting in a criss-cross pattern. See the Artwork Program User's Manual for convention definitions and examples.

The subroutines associated with the special plot options are NOTL, NPLOT, and SCAN. The function NBR is used by SCAN. Subroutine FILL is used in the normal fill option (option 3), but since its use has been described in the Outline-and-Fill section, it is not described here.

5.1 SUBROUTINE NOTL (NAP, DS, DL)

Subroutine NOTL is a new outline routine that is used in the outline and the dashed outline options (options 4 and 1). Its purpose is to use NPLOT, a new plot routine, to make plot outlines of polygons from XB and YB arrays in COMMON. The arguments of NOTL are not used in NOTL itself, but they must be passed on to NPLOT. Outlines generated by NOTL are always centered over the "ideal" polygon sides. These are different from the outlines generated by the FILL subroutine with BORMAX = 0.0 since there the outlines generated by FILL are always "shrunk" inside the polygons enough to correct for the outline width.

5.2 SUBROUTINE NPLOT (NAP, DS, DL)

When the space between dashes, DS, is set to zero NPLOT calls PLOT, the regular output routine, immediately. If DS is not

zero a dashed line is constructed between the last point plotted at coordinates (XOLDE, YOLDE) and the new end point at coordinates (X, Y). Using DS and DL (the dash length), the overall length of the dashed line to be drawn, an estimate is made of the number of dashes that will be necessary to draw the complete line segment. A certain amount of scaling is used on the dash length and dash spacing to insure that a dash occurs at each end of the segment to be drawn. This routine is short and can be understood easily from the commented listed.

5.3 SUBROUTINE SCAN (DY, THETA, NAP)

The SCAN subroutine generates the cross-hatch lines within a polygon. To define the arguments of SCAN, DY is the spacing between the cross-hatch lines, THETA is the angle of inclination of the cross hatch with the horizontal, and NAP is the aperture D-number that must be used during cross hatching.

Subroutine SCAN accepts polygon information through the COMMON arrays XB and YB. COMMON arrays XA and YA are given new names X and Y for use by subroutine SCAN. The COMMON variables that pass coordinates to the PLOT routine are called XI and YI to distinguish them from the normal names X and Y in the other routines.

The SCAN routine scans a polygon in a series of horizontal passes. The cross-hatch angle is introduced by rotating the entire polygon. Then, after horizontal scans are generated, they are rotated back to return the polygon to its original orientation.

In the method used to generate horizontal scans, vertices are processed starting with the highest and proceeding monotonically downward to the lowest. Scans are generated between vertices using information in the special arrays NHI and NLO. Prior to generation of a scan sequence, the NHI and NLO arrays are loaded with numbers identifying which polygon sides intersect the scan lines.

Figure 5.1 is a flowchart showing the sequence of operations in Subroutine SCAN.

5.4 CROSS-HATCH EXAMPLE

The processing of vertices consists of updating the arrays NHI and NLO. Before any sequence of scan lines can be generated, NHI

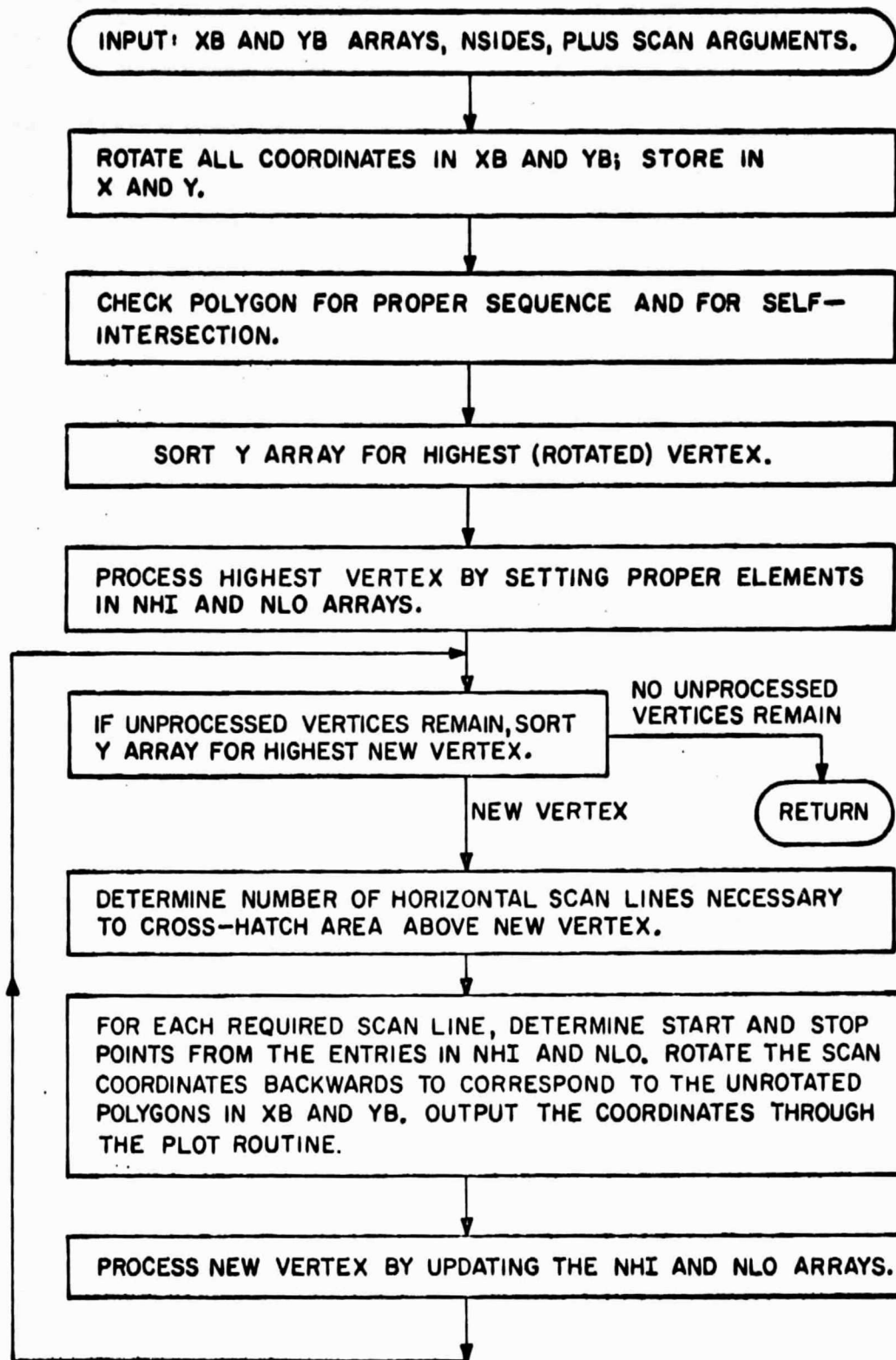


Figure 5.1 Subroutine SCAN

and NLO must identify the upper and lower end points of every polygon side that will intersect the lines to be generated. To simplify the explanation, consider the polygon shown in Figure 5.2.

The rotated coordinates X and Y would be stored and indexed by vertex number as shown by Table 5.1.

Table 5.1 Coordinates of Vertices

Vertex Number	1	2	3	4	5	6	7	8	9	10
X	2	1	5	6	8	8.5	5.5	8	7	4
Y	3	4	8	7	9	8.5	5.5	3	2	5

A search through the Y array reveals that vertex number 5 has the highest ordinate. The processing of this first vertex would result in the NHI and NLO entries of Table 5.2, where NLO shows the vertex number at the other ends of the line segments intersecting at vertex No. 5.

Table 5.2 Update Vertex No. 5

Entry No.	1	2
NHI	5	5
NLO	4	6

The two pairs entered indicate that scan lines immediately below the point just processed must intersect line segments from vertices 5 to 4 and from vertices 5 to 6.

Another search of the Y array would give the next lower vertex, No. 6. Using the information already stored in NHI and NLO, scan lines can be generated down to the level of vertex No. 6. The next update would result in Table 5.3.

Table 5.3 Update Vertex No. 6

Entry No.	1	2
NHI	5	6
NLO	4	7

Subsequent updates would bring about the following tables.

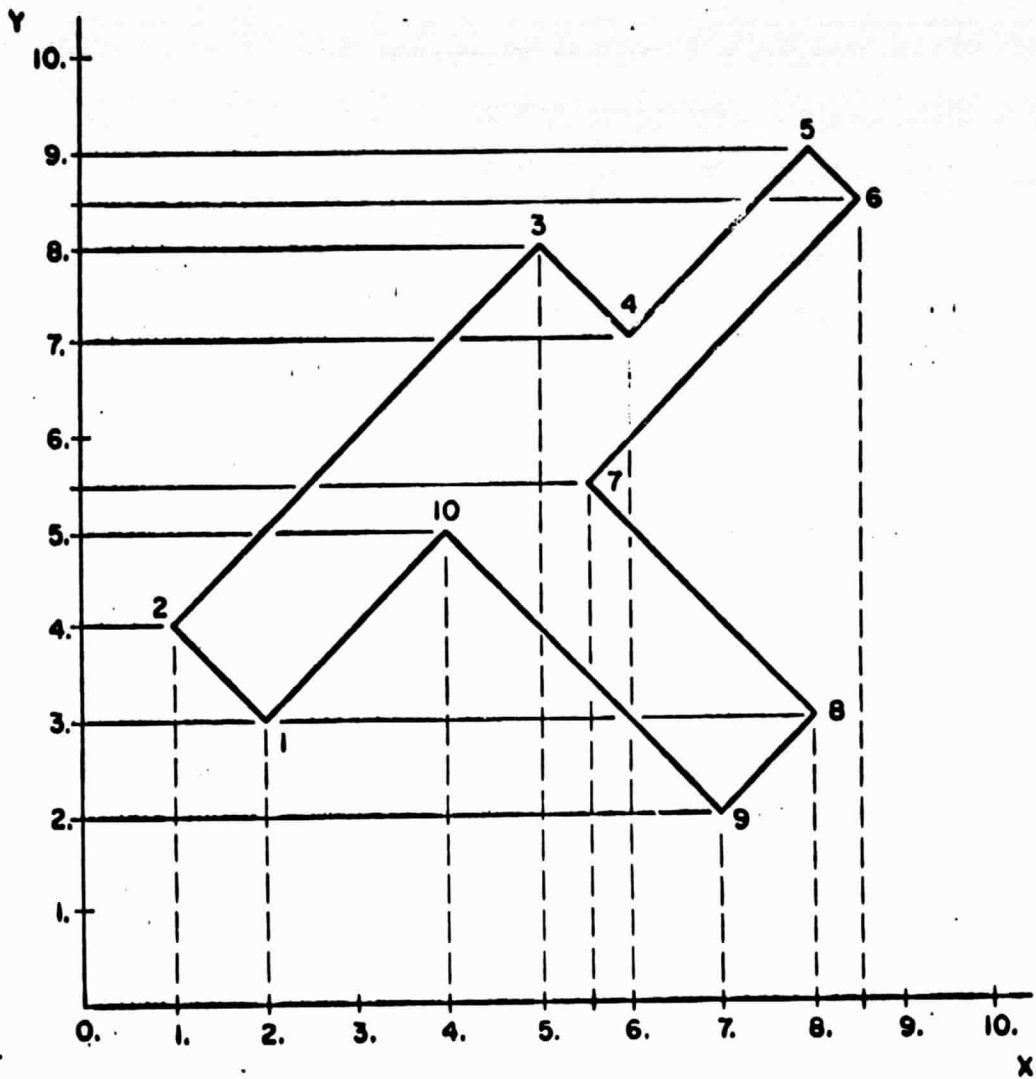


Figure 5.2 Rotated Polygon

Table 5.4 Update Vertex No. 3

Entry No.	1	2	3	4
NHI	3	3	5	6
NLO	2	4	4	7

Table 5.5 Update Vertex No. 4

Entry No.	1	2
NHI	3	6
NLO	2	7

Table 5.6 Update Vertex No. 7

Entry No.	1	2
NHI	3	7
NLO	2	8

Table 5.7 Update Vertex No. 10

Entry No.	1	2	3	4
NHI	3	10	10	7
NLO	2	1	9	8

5.5 THE UPDATE PROCESS

The updating of the NHI and NLO arrays, as each new vertex is encountered, is relatively complex. The action taken for a particular update depends on the orientation of the vertex causing the update. For instance, if the vertex causing the update is on an upward-pointing peak, the update consists of introducing two new element pairs into the NHI and NLO arrays. The two new pairs correspond to the two line segments (polygon sides) immediately below the vertex. A downward pointing peak causes two element pairs in NHI and NLO to be deleted.

Figure 5.3 shows all of the configurations that require different update procedures. Each one of the cases illustrated in Figure 5.3 contains either one isolated or two horizontal vertex points. In the three cases where two horizontal vertices are involved in an update, the update vertices are end points of a horizontal side.

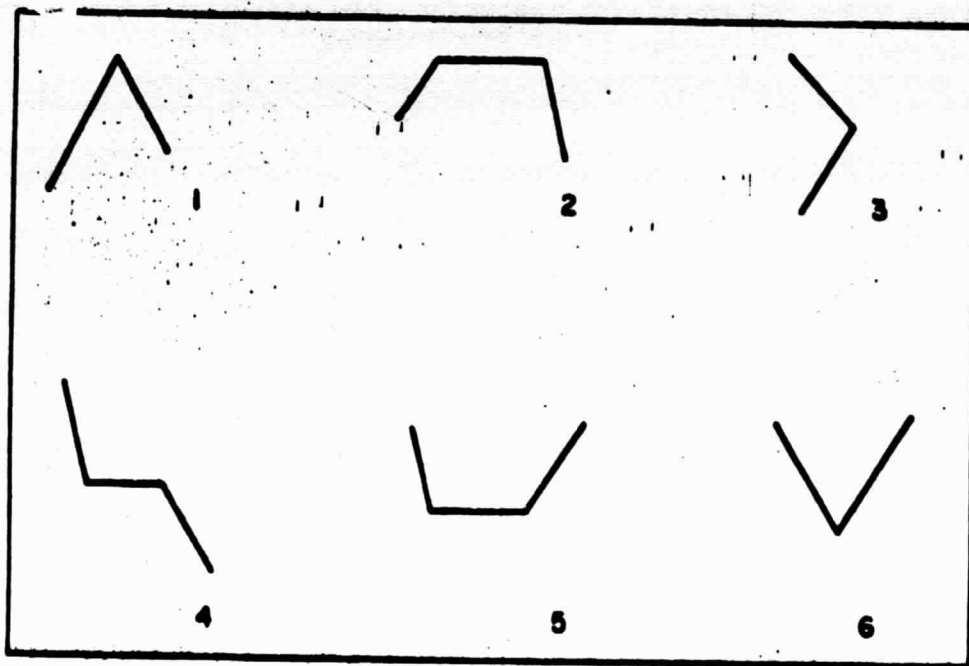


Figure 5.3 Update Configurations, Cases 1-6

When selection of a vertex makes an update necessary, it must be decided which of the six configurations of Figure 5.3 apply. Then the procedure that corresponds to that configuration must be used to bring about the update.

Figure 5.4 is an expansion of the lowest block in the flowchart of Figure 5.2. It demonstrates the procedure used to detect and update the cases of Figure 5.3. The procedure used here detects case 4 in one of two ways (causes 4A and 4B), depending upon which end point of the horizontal segment of case 4 is selected by the computer during the Y-coordinate search operation. Further details can be obtained from the comments in the SCAN listing.

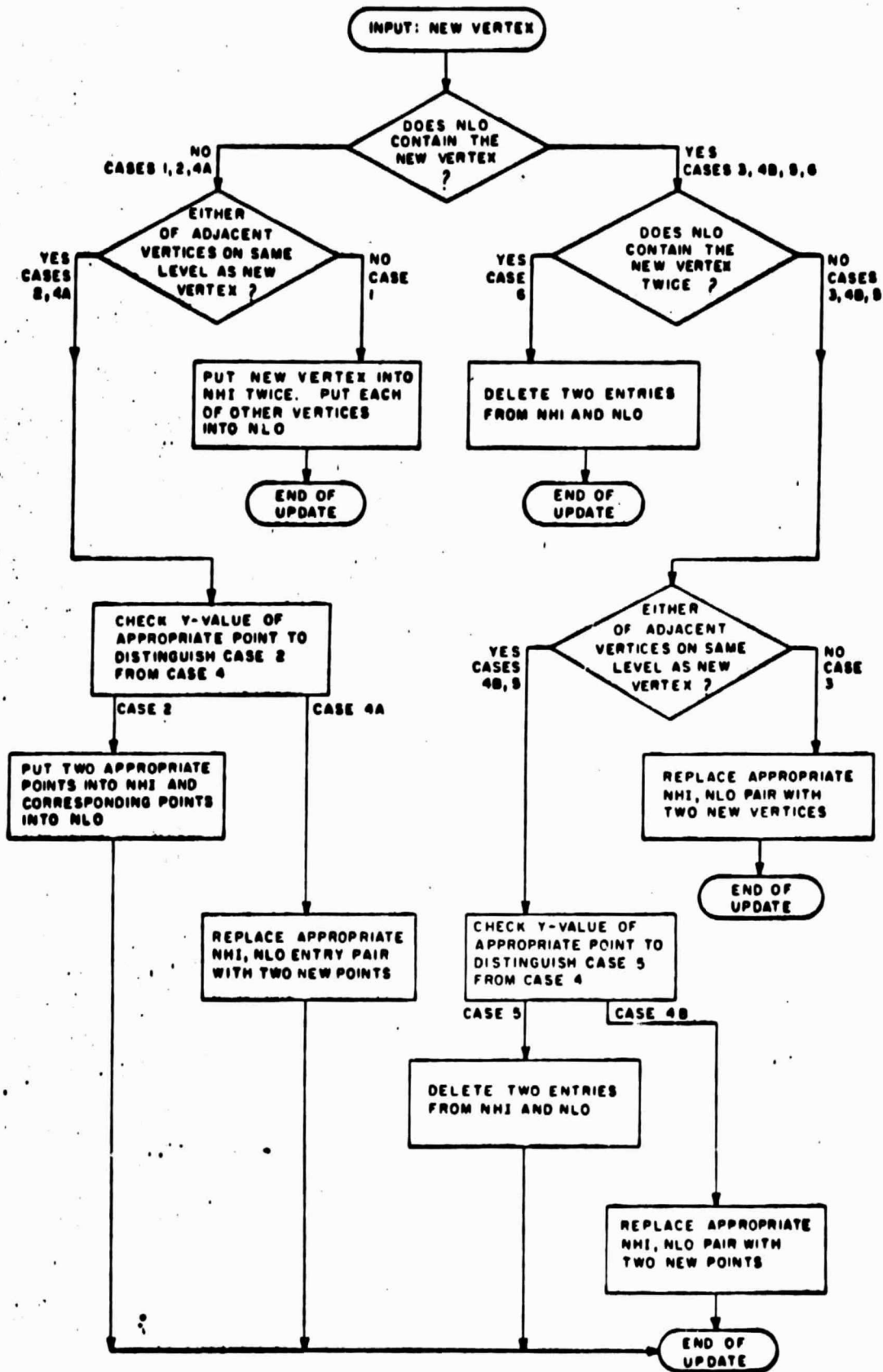


Figure 5.4 Update Flowchart